

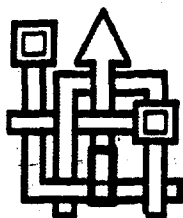
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Gate-All-Around Device

Final technical report (RHD-04)

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13. ABSTRACT (Maximum 200 words) The gate-all-around device is an SOI MOS field-effect transistor. The gate electrode and the thin gate oxide are wrapped around the active channel region. No other insulator (field oxide or buried oxide) is in contact with the active region of the device. The gate-all-around device exhibits a high transconductance (up to 4 times that of a normal SOI transistor), an ideally sharp subthreshold slope, and demonstrates the concept of volume inversion in the SOI films. Both n-channel and p-channel devices have been fabricated.				
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1. Description of the problem

SOI MOSFETs are known for their potential for application in circuits operating in harsh environments and have been shown to exhibit superior performances in high-temperature and ionizing environments. The resistance of SOI devices to alpha particle and heavy ion impact (SEU) is inversely proportional to the volume of silicon in which the device is made, *i.e.* inversely proportional to the thickness of the SOI layer. The same dependence on film thickness is expected for gamma-dot phenomena, for the same reasons¹.

The problem preventing one from utilizing thin-film, fully depleted devices for rad-hard applications is the poor total dose immunity of thin-film devices.² Indeed, as charges accumulate in the buried oxide layer upon irradiation, several problems do arise: at first, front threshold voltage shifts appear, due to the coupling between front and back gate depletion zones, and secondly, back-channel leakage appears as the back oxide charge density becomes too high.

The effect of total dose on the device properties depends on the thickness of the oxide in contact with the silicon. A much larger amount of oxide charges are generated in a SIMOX buried oxide, for instance, than in the gate oxide. The charge generated, ΔQ_{ox} , is roughly proportional to the oxide thickness. In addition, the threshold shift generated by oxide charges, ΔV_{th} , is also proportional to the oxide thickness. In consequence, back threshold voltage shift is roughly proportional to the square of the oxide thickness

($\Delta V_{th} \cong \frac{\Delta Q_{ox} t_{ox}}{\epsilon_{ox}}$, with $\Delta Q_{ox} \cong t_{ox}$). The accumulation of charges in the buried oxide induces a shift of the front-side threshold voltage as well because of the electrical coupling present between the front and the back gate in thin-film fully depleted devices. An obvious way of minimizing the effects of total-dose exposure is to reduce the thickness of the oxide layers surrounding the active silicon. Unfortunately, no practical means have been found as yet to produce thin, gate-quality buried oxides. Buried oxides have typical thicknesses of 400 nm or 1 μm , when produced by the SIMOX or ZMR techniques, respectively.

2. The Gate-All-Around Device

The solution proposed by the gate-all-around device consists in surrounding the whole active area of the transistor with thin, gate-quality oxide. This gate oxide is itself surrounded by the polysilicon gate electrode, which provides ground potential when the device is turned OFF.

The work performed last year (see the first annual technical report (RHD-02)) has resulted in the publication of several scientific articles, one of which in association with the NRL, Washington D.C., and DNA, Alexandria, VA. These publications are:

-
- 1 J.P. Colinge, *Silicon-On-Insulator Technology: Materials to VLSI*, Kluwer Academic Publishers, p. 178, 1991
 - 2 D.C. Mayer, "Modes of operation and radiation sensitivity of ultrathin SOI transistors", *Proceedings of the IEEE SOS/SOI Technology Conference*, pp. 52-53, 1989

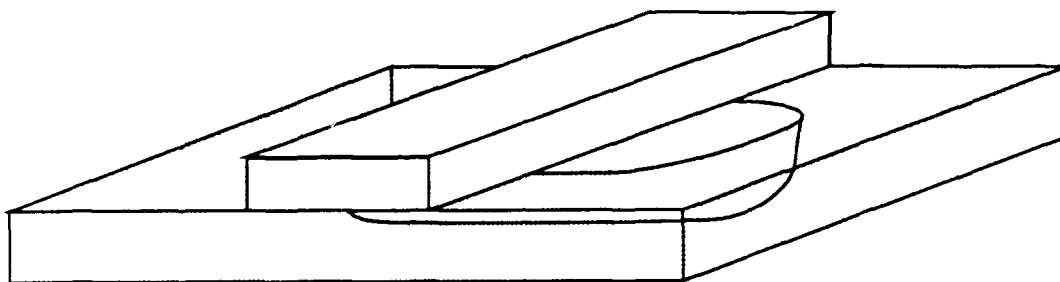
- "Silicon-on-insulator gate-all-around device", J.P. Colinge, M.H. Gao, A. Romano, H. Maes, and C. Claeys, Proc. IEEE SOS/SOI Technology Conf., p. 137, Oct. 1990
- "Silicon-on-insulator gate-all-around device", J.P. Colinge, M.H. Gao, A. Romano, H. Maes, and C. Claeys, IEDM, P. 595, 1990
- "Radiation effects in gate-all-around structures", R.K. Lawrence, J.P. Colinge, H.L. Hughes, and G.E. Davis, Proceedings IEEE International SOI Conference, 1991, p. 80
- "An analytical model for GAA transistors", A. Terao and F. Van de Wiele, Microelectronic Engineering 15, (1991), pp. 233-236
- "Characteristics of nMOS/GAA transistors near threshold", P. Francis, A. Terao, D. Flandre and F. Van de Wiele, paper accepted for ESSDERC (European Solid-State Research Conference), 1992
- "High temperature characteristics of GAA/SOI transistors and circuits", P. Francis, A. Terao and D. Flandre, submitted to the IEEE International SOI Conference, 1992
- "Low-frequency behaviour of GAA SOI transistors", E. Simoen, U. Magnusson, C. Claeys, and J.P. Colinge, submitted to the IEEE International SOI Conference, 1992

3. Process Description

3.1. N-channel devices

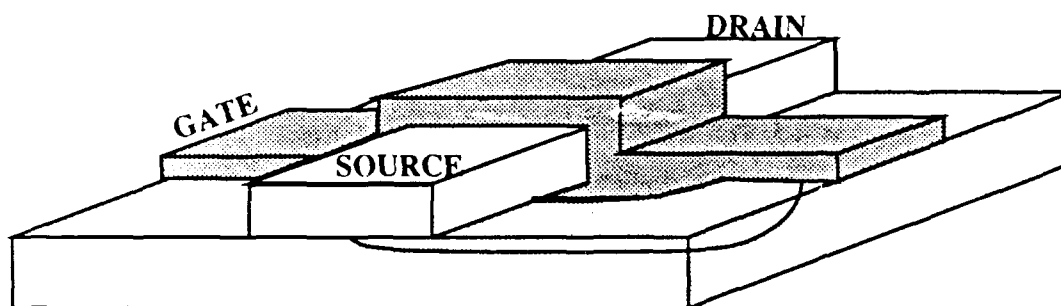
The process starts with standard SIMOX wafers. The thickness of the starting silicon film is 180 nm. A 60 nm-thick pad oxide is grown, and a 200 nm-thick film of silicon nitride is deposited. A mask step is used to pattern the nitride as well as the silicon film in a dry etch reactor. Using the nitride as a mask, 600 nm of oxide are grown on the edge of the silicon island. Such an oxidation as for consequence to smooth the edges of the silicon island and has been reported to be useful to improve gate oxide breakdown properties.³ The nitride and the pad oxide are then wet etched, and a second masking step is used to define areas where the underlying oxide (as well as the edge oxide) will be etched. Etching of the buried silicon leaves a beam (bridge) of silicon free-standing over a cavity (Figure below) The silicon bridge is supported at both ends by the original buried oxide. The free-standing part of the silicon island will later on become the active part of the device (the channel region), while those parts still supported by the underlying oxide will become the source and the drain.

³ M. Haond *et al.*, "Gate oxide breakdown behaviour in a mesa SOI CMOS process", Proceedings of the IEEE SOS/SOI Technology Conference, pp. 68-69, 1989



Gate-All-Around device after etching of a cavity underneath the silicon island

A thick thermal gate oxide is then grown at 850°C in dry oxygen. Its thickness is either 50 nm (in one split) or 30 nm (in another split). Boron is there implanted to adjust threshold voltage. A 450 nm-thick polysilicon film is then deposited in a LPCVD furnace at a temperature of 620°C. Because of the excellent conformal deposition of LPCVD polysilicon, gate material is deposited not only at the top of the device, but also in the cavity below the silicon bridge. Polysilicon is, hence, deposited all around the gate oxide which itself is grown all around the channel region of the silicon island (hence the name: Gate-All-Around Device.) The polysilicon film is then implanted with phosphorous ions, and a long (4 hours) annealing step is used to diffuse the phosphorous everywhere in the polysilicon, even underneath the silicon bridge, where no ions are implanted. The polysilicon is then etched using a mask step to define the gate, after which phosphorous is implanted to form self-aligned sources and drains (Figure below) After source and drain anneal, low temperature oxide is deposited, and contact hole are etched. A standard metallization step completes the process. Care is taken not to use steps at temperatures higher than 800°C after the gate oxide has been grown.



Gate-All-Around device after source and drain formation

3.2. P-channel devices

The process starts with standard SIMOX wafers. The thickness of the starting silicon film is 180 nm. A 60 nm-thick pad oxide is grown, and a 200 nm-thick film of silicon nitride is deposited. A mask step is used to pattern the nitride as well as the silicon film in a dry etch reactor. Using the nitride as a mask, 600 nm of oxide are grown on the edge of the silicon island. Such an oxidation as for consequence to smooth the edges of the silicon island and has been reported to be useful to improve gate oxide breakdown properties. The nitride and the pad oxide are then wet etched, and a second masking step is used to define areas where the underlying oxide (as well as the edge oxide) will be etched. Etching of the buried silicon leaves a beam (bridge) of silicon free-standing over a cavity. The silicon bridge is supported at both ends by the original buried oxide. The free-standing part of the silicon island will later on become the active part of the device (the channel region), while those parts still supported by the underlying oxide will become the source and the drain. A thick thermal gate oxide is then grown at 850°C in dry oxygen. Its thickness is 50 nm. Boron is there implanted to adjust threshold voltage. A 450 nm-thick polysilicon film is then deposited in a LPCVD furnace at a temperature of 620°C. Because of the excellent conformal deposition of LPCVD polysilicon, gate material is deposited not only at the top of the device, but also in the cavity below the silicon bridge. Polysilicon is, hence, deposited all around the gate oxide which itself is grown all around the channel region of the silicon island (hence the name: Gate-All-Around Device.) The polysilicon film is then implanted with phosphorous ions, and a long (4 hours) annealing step is used to diffuse the phosphorous everywhere in the polysilicon, even underneath the silicon bridge, where no ions are implanted. The polysilicon is then etched using a mask step to define the gate, after which phosphorous is implanted to form self-aligned sources and drains. After source and drain anneal, low temperature oxide is deposited, and contact holes are etched. A standard metallization step completes the process. Care is taken not to use steps at temperatures higher than 800°C after the gate oxide has been grown.

A lithography with minimum feature size of 3 μm was used for the process. Similar devices were made without etching a cavity underneath the silicon island. These devices are thus classical SOI MOSFETs, and can be used for comparing the electrical properties of Gate-All-Around devices and classical SOI MOSFETs, both before and after exposure to ionizing radiations.

The next page presents the SUPREM-III simulation files used to model the Gate-All-Around fabrication process as well as the result of PISCES-IIb simulation of the device behaviour.

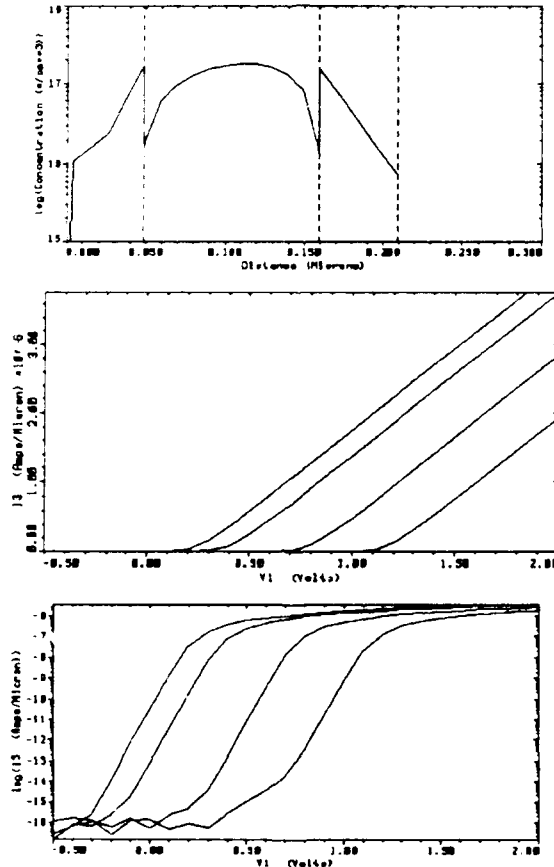
3.3. Process simulation for the GAA device

```

title gaa 180 nm n-ch
init oxide thick=.05 dx=.1 spaces=50
deposit silicon <100> thick=0.18
diffusion time=85 temp=1000 dryo2
print layers
deposit nitride thick=.2
diffusion time=400 temp=1000 weto2
etch oxide.th
etch nitride
etch oxide.th
diffusion temp=850 time=660 dryo2
print layers
etch oxide.th
diffusion temp=850 time=660 dryo2
implant boron energy=30 dose=8,10,15,20e11
diffusion temp=800 time=240
diffusion temp=820 time=300
print layers
savefile file=supn1.out device
plot chemical phosphorus top=1e18 bottom=1e15 y.logar right=0.3
+ device=regis
plot chemical boron add pause
stop

```

n-ch 3µm 180nm, box=50nm, GAA



Suprem simulation of the impurity profile (top) and Pisces simulation of the n-channel devices (middle and bottom top). The Suprem input file is listed above.

3.4. Process flow chart

Macro Step Description	WAFER				
	7	8	9	10	11
SIMOX=S, BULK P-CH=P, NCH=N, TEST=T	S	S	S	S	S
Get 10 SIMOX wafers from JP Colinge	x	x	x	x	x
Get 5 bulk wafers, p-type <100>, 10-25 ohm.cm					
Get 5 bulk wafers, n-type <100>, 4-6 ohm.cm					
Label SIMOX wafers with numbers 7 to 16	x	x	x	x	x
Label p-type bulk wafers wafers with numbers 1 to 3, and 17 and 19					
Label n-type bulk wafers wafers with numbers 4 to 6, and 18 and 20					
Measure thickness of SIMOX wafers with UV/vis reflectance	x	x	x	x	x
grow 100 nm of oxide	x	x	x	x	x
strip oxide in BHF	x	x	x	x	x
Measure thickness of SIMOX wafers with UV/vis reflectance	x	x	x	x	x
grow 31 nm of oxide	x	x	x	x	x
strip oxide in BHF					
Measure thickness of SIMOX wafers with UV/vis reflectance					
Pad oxidation: grow 30 nm, dry oxygen, 1000C					
Measure pad oxide thickness on wafers 22 to 25					
Deposit 200nm nitride	x	x	x	x	x
Measure nitride thickness					
*** Litho: active area *** Canon exposure, develop, hardbake	x	x	x	x	x
Plasma etch 200nm of nitride	x	x	x	x	x
Etch 30nm pad oxide in BHF (dewetting on bulk)	x	x	x	x	x
Wet/dry resist strip	x	x	x	x	x
*** Litho: n-channel mask *** Canon, develop, hardbake					
Field implant: Boron, 50 keV, 4e14	x	x	x	x	
Wet/dry resist strip					
anneal in N2, 950C, 90 min	x	x	x	x	
0.13 μ m trench etch in silicon (stop on oxide)	x	x	x	x	x
Field oxidation: grow 400nm steam 1000C	x	x	x	x	x
Field oxidation: grow 600nm steam 1000C					
Inspect field oxidation	x	x	x	x	x
Wet etch oxide on nitride (20 sec BHF)	x	x	x	x	x
Wet etch 200nm nitride	x	x	x	x	x
Wet etch 30nm pad oxide	x	x	x	x	x
Implant phosphorus 100keV 1e11					
Gate oxidation: 50 nm @ 850 C, steam					
implant boron 25 keV 1e11					
*** Litho: n-channel mask *** Canon, develop, hardbake					
Implant boron 170 keV 1e12					
implant boron 60 keV 2.5e11					
implant boron 60 keV 3e11					
Strip resist					

*** Litho: ETCH mask *** Canon, develop, hardbake	x	x	x	x	x
Oxide etch in BHF by JPC	x	x	x	x	x
resist strip (NO ULTRASOUNDS!!!)	x	x	x	x	x
Gate oxidation: 30 nm @ 850 C, steam	x				
Gate oxidation: 50 nm @ 850 C, steam		x	x	x	x
Measure gate oxide thickness					
implant boron 25 keV 1.5e12		x			
implant boron 25 keV 2e12			x		
implant boron 25 keV 2.5e12	x			x	
implant phosphorus 60 keV 1e11					x
implant boron 30 keV 6e11					
implant boron 30 keV 8e11					
implant boron 30 keV 1e12					
deposit polysilicon, thickness=450nm	x	x	x	x	x
measure polysilicon thickness					
implant phosphorus 50 keV, 1e16	x	x	x	x	x
annealing: 45 min @ 800 C in N2					
annealing: 240 min @ 800 C in N2	x	x	x	x	x
Etch native oxide on poly in HF (dewetting)	x	x	x	x	x
measure polysilicon sheet resistivity					
*** Litho: poly gate mask mask *** Canon, develop, hardbake	x	x	x	x	x
Polysilicon plasma etch (thickness=450nm)	x	x	x	x	x
strip resist (NO ULTRASOUNDS!!!)	x	x	x	x	x
measure remaining oxide thickness (on source & drain)					
thin S&D oxide to 20 nm in HF 2%	x	x	x	x	x
*** Litho: n-channel mask *** Canon, develop, hardbake					
implant phosphorus 70 keV 4e15	x	x	x	x	
strip resist					
*** Litho: p-channel mask *** Canon, develop, hardbake					
implant boron 25 keV 4e15					x
resist strip					
S&D anneal:180 min @ 800 C in N2	x	x	x	x	x
deposit 600 nm undoped TEOS	x	x	x	x	x
densify 30 min @ 800C in O2					
*** Litho: contact holes mask *** Canon, develop, hardbake	x	x	x	x	x
etch oxide in BHF; note time to dewetting					
wet etching contact holes in BHF	x	x	x	x	x
strip resist (NO ULTRASOUNDS!!!)	x	x	x	x	x
Al/Si sputtering: thickness=1 µm	x	x	x	x	x
*** Litho: metallization mask *** Canon, develop, hardbake	x	x	x	x	x
Plasma etch metal + inspection	x	x	x	x	x
resist strip in microstrip	x	x	x	x	x
sintering 3 wafers forming gas 420C + call JPC	x				
sintering forming gas 420C + call JPC	x	x	x	x	x
END	x	x	x	x	x

Process flow for the GAA device

The detailed process is given in ANNEX I

3.5. Process splits

As can be seen in the process flow, all devices were realized in thin-film SOI (contrarily to the devices in the first annual technical report (RHD-02)), where both thick-film and thin-film devices were made).

- Wafers 8, 9 and 10 contain n-channel devices, and the gate oxide thickness is 50 nm (500 Å).
- Wafer 7 contains n-channel devices, and the gate oxide thickness is 30 nm (300 Å).
- Wafers 11 contains p-channel devices, and the gate oxide thickness is 50 nm (500 Å).

Wafer ID	7	8	9	10	11
gate oxide thickness	30 nm	50 nm	50 nm	50 nm	50 nm
N or P channel	N	N	N	N	P

Process splits

4. Device results

All wafers yielded devices with the expected characteristics. The yield, when the devices were probed at the wafer level, was almost 100%.

The electrical characteristics of the GAA devices from the second run (one set of curves for each split) are reported in **ANNEX II**.

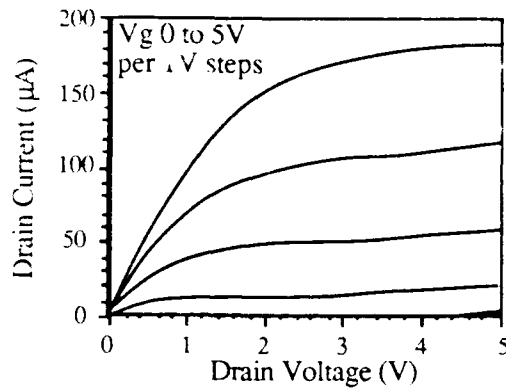
These characteristics are:

- $I_D(V_G)$ for $V_{DS} = 100$ mV, with both linear and logarithmic vertical scales (top left Figure)
- $I_D(V_{DS})$ for $V_G = 0$ to 5 volts, (bottom left Figure)
- Transconductance (g_m) at $V_{DS} = 100$ mV, as a function of gate voltage (bottom right Figure)

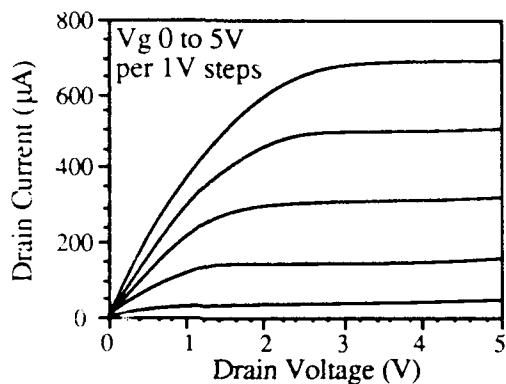
All observations made previously (see the first annual technical report (RHD-02)) about the sharp subthreshold slope, the high transconductance and the volume inversion phenomenon are still holding for the present devices. The novelties of the devices from the second run (compared to the previous fabrication run) are the presence of a thinner gate oxide (30 nm), and that of p-channel devices. The particularities of the GAA device physics (from report RHD-02) are recalled in Section 4.1 below.

4.1 Device physics

The two Figures below present the output characteristics of a conventional n-channel SOI MOSFET and a gate-all-around n-channel device. The final silicon thickness of the conventional device is 125 nm, while the thickness of the GAA device is 100 nm (the GAA device is thinner because gate oxide was grown on both front and back interfaces of the silicon film). The SOI MOSFET is partially depleted. Both devices have the same (drawn) physical dimensions ($W/L=3\mu\text{m}/3\mu\text{m}$), but, because of the presence of two channels (at the top and bottom of the silicon film), the effective width of the GAA device is $6\mu\text{m}$.

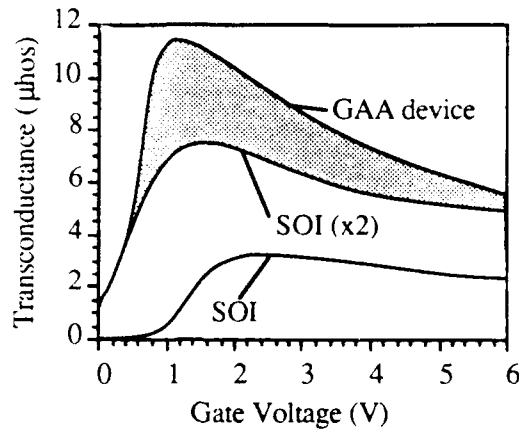


Output characteristics of a "normal" n-channel SOI MOSFET. $(W/L)_{\text{mask}} = 3\mu\text{m}/3\mu\text{m}$.



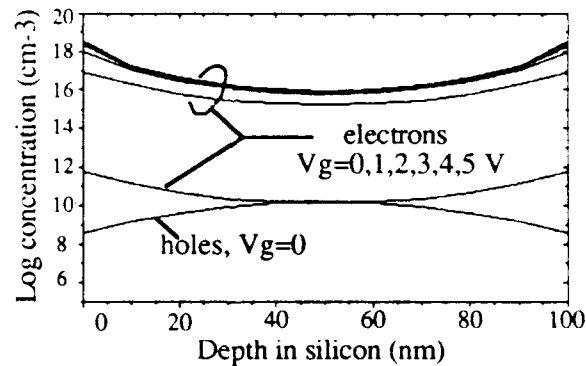
Output characteristics of an n-channel GAA device. $(W/L)_{\text{mask}} = 3\mu\text{m}/3\mu\text{m}$.

It can be observed that the current drive is much higher in the GAA device than in the SOI transistor. The increased drive is, of course, partly due to the larger effective width ($6\mu\text{m}$ instead of $3\mu\text{m}$) and to the lower threshold voltage (V_{th} is lower in the GAA device (0.45 V) than in the SOI MOSFET (1.2 V) because of the thinner silicon film and because of the interaction between the top and bottom depletion zones). But another effect has to be taken into consideration to fully account for the increased drive. This effect is called "volume inversion".⁴ It can clearly be observed in the Figure below where the transconductance of a conventional device and that of a GAA device are compared. An additional curve labelled "SOI x 2" presents the transconductance of the SOI MOSFET multiplied by two and shifted to the left by the difference of threshold voltages ($V_{\text{th,SOI}} - V_{\text{th,GAA}}$) to account for both the presence of two channels and the lower threshold voltage of the GAA device. The grey area represents the extra drive of the GAA device, which is attributed to volume inversion.



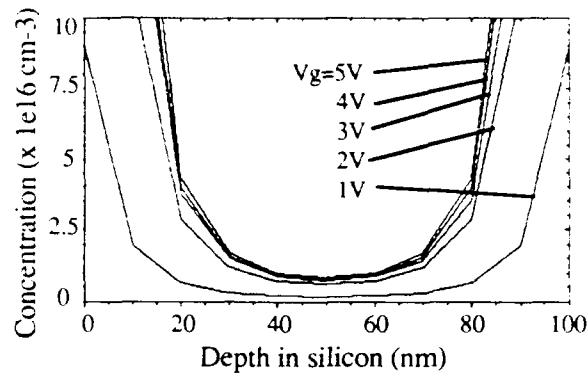
Transconductance (dI_d/dV_G) at $V_{ds}=100$ mV in a conventional SOI MOSFET and a GAA device. $(W/L)_{mask} = 3\mu\text{m} / 3\mu\text{m}$.

The Figure below shows that the electron concentration at all depths in the silicon film is much larger than the hole concentration, for all positive gate voltages. The contribution of volume inversion is more pronounced right above threshold, where the inversion layer is distributed across the entire silicon film and where the effects of bulk mobility (in contrast to surface mobility) can be felt.



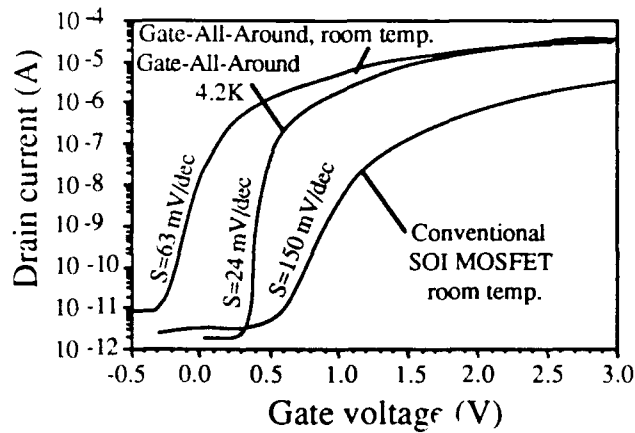
Carrier distribution as a function of depth in silicon for different gate voltages.

At higher gate voltages, there is still inversion in the centre of the silicon film, but the carriers are now mostly localized in inversion layers near the interfaces. As a result, more scattering occurs, and the transconductance tends to be equal to twice that of that a conventional device.



Electron concentration as a function of depth in silicon for different gate voltages.

Because of the excellent coupling between the surface potentials and the gate voltage, a subthreshold slope of 63 mV/decade is obtained at room temperature (vs. 150 mV/decade in the conventional, partially depleted SOI device). Device measurements were carried at liquid helium temperature (4.2 K) as well. As it was the case at room temperature, no kink is observed in the output characteristics, and the output characteristics are flat (high output impedance). At 4.2 K the subthreshold slope is equal to 24 mV/decade and the threshold voltage is 1.1 V (vs. 0.45 V at room temperature).

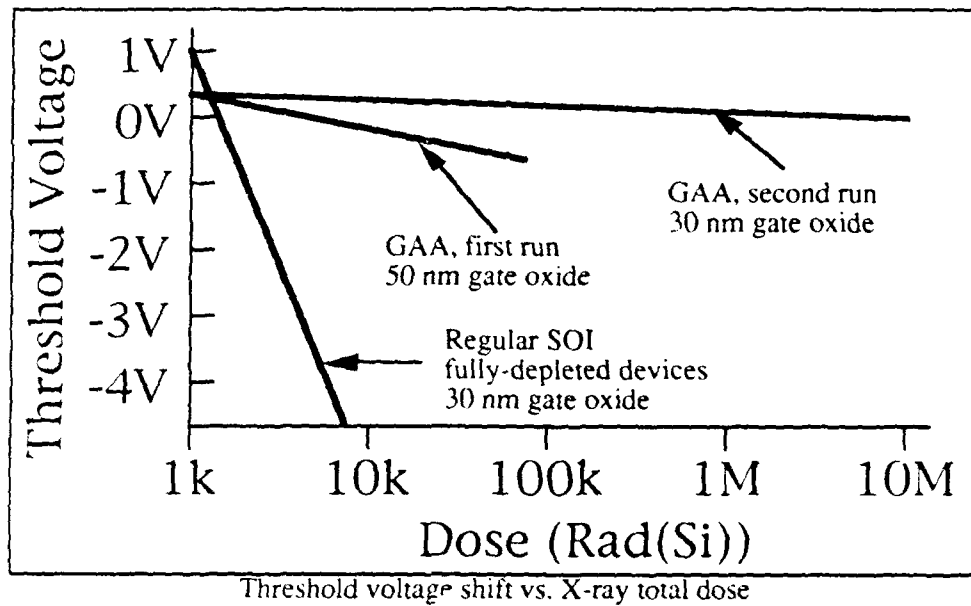


Log of current as a function of gate voltage ($V_{DS}=100 \text{ mV}$).

The layout of the chip used for device fabrication and the dimensions of the different devices are reported in ANNEX III.

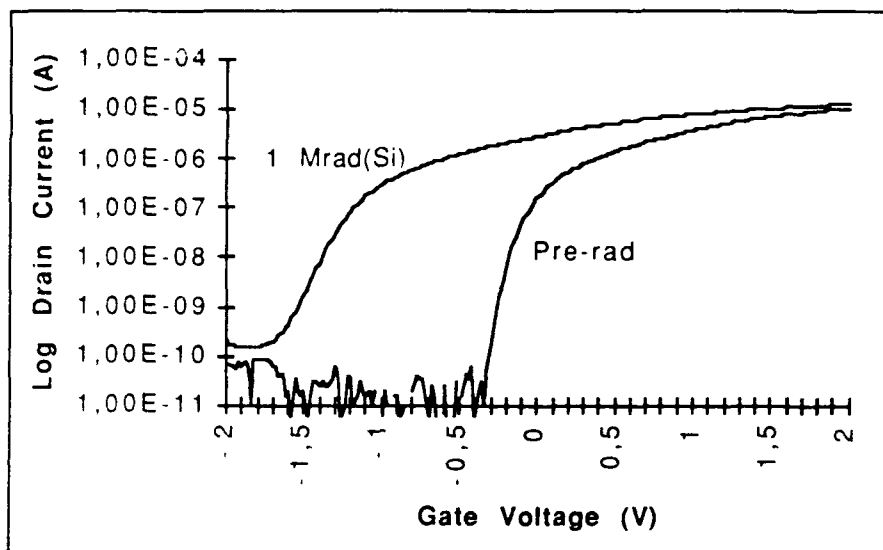
5. Irradiation results

The goal of improving the radiation hardness has been achieved since the device show almost no degradation and only a 200 mV threshold voltage shift after exposure to 10 Mrad(Si) of X-rays ⁵ (ARACOR irradiation equipment). The results of these irradiation tests is presented in the Figure below.



⁵ R. Lawrence, Aracor, private communication

N-channel devices with a 30 nm gate oxide were irradiated using a ^{60}Co source in the Nuclear Sciences Department of the Université Catholique de Louvain (Belgium). Here are the results of such an irradiation test, carried out on a $3\mu\text{m} \times 3\mu\text{m}$ n-channel device with a gate oxide thickness of 30 nm. The gate bias used during irradiation is +2 volts. Little leakage is observed after irradiation. The threshold shift is 1 volt, and corresponds to a hole trapping factor value of 0.08.



Logarithm of drain current vs. gate voltage on a $3\mu\text{m} \times 3\mu\text{m}$ n-channel device with a gate oxide thickness of 30 nm

6. Packaged devices

Packaged devices are provided along with the present report. These devices are n- and p-channel Gate-all-around transistors and n- and p-channel regular thin-film SOI MOSFETs fabricated using the same process as the GAA devices (with the exception of the cavity etch). The Table below indicates the different types of devices found in **each** package.

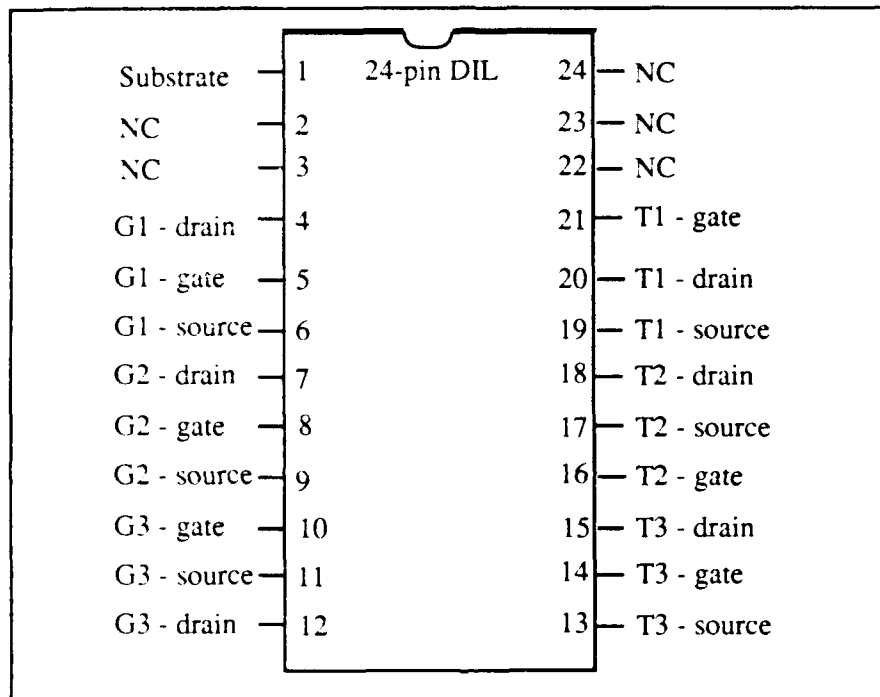
Name	Size (L/W)	Type device
G1	3/3 μm	GAA device
G2	3/4 μm	GAA device
G3	5/4 μm	GAA device
T1	3/3 μm	NMOS / PMOS
T2	3/4 μm	NMOS / PMOS
T3	5/4 μm	NMOS / PMOS

Devices in each package. G1, G2 and G3 are GAA devices, T1, T2 and T3 are regular thin-film SOI transistors.

It is worthwhile noting that each package contains only a chip from one of the process splits. Therefore each package contains devices with either a 30 nm or a 50 nm gate oxide, and contains either n- or p-channel devices, not both.

Quarter of wafers from each splits (unpackaged devices) have been mailed as well to Dr. Harold Hughes, Naval Research Labs, Washington D.C.

The bonding pad configuration of the chips is presented below. 24-pin DIL packages have been used. Pin #1 is connected to the silicon substrate (the back gate of the regular SOI transistors). The notations are self-explanatory. For instance, pin #4 is connected to the drain of the GAA device #1, and so on. The device names (G1, G2, G3, T1, T2 and T3) refer to the Table on the previous page.



Pin layout of the packages devices

Although all devices were functional prior to bonding, we noticed that some were degraded or destroyed after bonding. The wire-bonding machine of IMEC was indeed experiencing ESD problems at the time where these devices were packaged. As a result, some devices in the packages have lost their functionality. After bonding, all devices were re-tested in order to establish the three Tables below.

The devices which "survived" the bonding may also have been affected, in some way, by the ESD problem. Therefore, **we recommend that no voltage larger than 3 volts be used on any terminal of the devices (gate, drain or back gate). This is especially true for the devices with the thinner gate oxide (wafer #7).**

Wafer #7
NMOS, 30nm gate oxide

Package no.	Device name					
	G1	G2	G3	T1	T2	T3
7 - 1	X	X	X	X	X	X
7 - 2	OK	OK	X	X	OK	OK
7 - 3	OK	OK	X	OK	X	OK
7 - 4	OK	OK	OK	OK	OK	OK
7 - 5	X	OK	X	OK	OK	OK
7 - 6	OK	X	OK	OK	OK	OK
7 - 7	X	OK	OK	OK	OK	OK
7 - 8	X	X	X	X	OK	OK
7 - 9	X	X	OK	X	OK	OK
7 - 10	X	OK	OK	X	X	OK
7 - 11	X	OK	X	OK	X	X
7 - 12	X	X	X	X	X	X
7 - 13	OK	X	OK	X	OK	OK

Bonding functionality for packages from wafer 7 (n-channel devices with 30 nm-thick gate oxide. "OK" means that the device works fine, and "X" means that the device has been degraded by ESD during bonding.

Wafer #10
NMOS, 50nm gate oxide

Package no.	Device name					
	G1	G2	G3	T1	T2	T3
10 - 1	X	OK	OK	X	OK	OK
10 - 2	OK	OK	OK	OK	OK	OK
10 - 3	X	OK	OK	X	X	X
10 - 4	X	OK	OK	OK	OK	OK
10 - 5	X	OK	OK	OK	OK	OK
10 - 6	OK	OK	OK	OK	OK	OK
10 - 7	X	X	OK	X	OK	OK
10 - 8	X	OK	OK	OK	OK	OK
10 - 9	OK	X	OK	OK	OK	OK
10 - 10	X	OK	OK	X	OK	OK
10 - 11	X	OK	OK	X	OK	OK
10 - 12	OK	OK	OK	X	OK	OK
10 - 13	OK	OK	OK	X	OK	OK

Bonding functionality for packages from wafer 10 (n-channel devices with 50 nm-thick gate oxide. "OK" means that the device works fine, and "X" means that the device has been degraded by ESD during bonding.

Wafer #11
PMOS, 50nm gate oxide

Package no.	Device name					
	G1	G2	G3	T1	T2	T3
11 - 1	X	OK	OK	X	OK	OK
11 - 2	OK	OK	OK	OK	OK	OK
11 - 3	X	OK	OK	OK	OK	OK
11 - 4	X	OK	OK	OK	X	OK
11 - 5	X	OK	OK	OK	OK	OK
11 - 6	OK	OK	OK	OK	OK	OK
11 - 7	X	OK	OK	OK	OK	X
11 - 8	X	OK	OK	OK	OK	OK
11 - 9	X	OK	OK	OK	OK	OK
11 - 10	X	OK	OK	OK	OK	OK
11 - 11	X	OK	OK	OK	OK	OK
11 - 12	X	OK	OK	OK	OK	OK
11 - 13	X	OK	OK	OK	OK	OK

Bonding functionality for packages from wafer 11 (p-channel devices with 50 nm-thick gate oxide. "OK" means that the device works fine, and "X" means that the device has been degraded by ESD during bonding.

PROCESS FLOW

The following pages describe in detail the different steps of the fabrication process

Lot number : PLINE240/1
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

SPLIT LOT 0900 27/03/91
 SPLT
 MVNS

CANON PR 4 6104 27/03/91
 MVOU CANON

# WAFERS	5
# TIMES	1
DEHYD TEMP	200
SOFTBAK TEMP	110
PHOTORESIST	S1713
MASK ID	SOI ETCH
EXPOSE TIME	39.00
SUBSTRATE	SI02/SI
D.U.V. TIME	5.00
POSTBAKETEMP	150
POST METHOD	OVEN
DEVELOPMENT	TRACK
RESIST_SPEED	4300
VISUAL_INSP	PASS
OXYGEN FLASH	NO

INSP PH 4 7314 28/03/91
 MVOU MICROSCOPE

# WAFERS	5
PPI EXAMINE	50
PPI PASS	50
PPI FAIL	
PPI MARGINAL	
PPI ACTION	PASS

WETCH OX 7104 28/03/91
 MVOU WET BENCH

# WAFERS	5
WETETCHSTUFF	THOX
WET ETCHANT	BHF
TEMPERATURE	
DEVICEWAFER	
DEVWAFETCHIM	

COMMENT : BHF: 20' - BAKE:130C 20' OVEN - BHF:5' - BHF:10'

Lot number : PLINE240/1
Product : SOI 3UM CMOS
Route : GW_S3CMOS1

DRY US STR 7424 29/03/91
MVOU PRS800

# WAFERS	5
DRYSTRIP TIME	30.00
E STRIP TEMP	137.00
WETSTRIPSTUF	MICRO2001
WETSTRIP TIME	30
ULTRASON PWR	.0
VISUAL INSP	PASS

G_DOX 975 8436 29/03/91
MVOU I-4

# WAFERS	2
FUR TYPE	DRY
DRY OXIDTEMP	975
DRY OXID TIM	40
STANDARD RAMP	YES
TEST WAFER ID	SYSTEM
MEAN THICK	28.5
S.D. THICK	.7

READ ME 7010 03/04/91
MVOU

G_DOX 975 8437 04/04/91
MVOU I-4

# WAFERS	2
FUR TYPE	DRY
DRY OXIDTEMP	975
DRY OXID TIM	90
STANDARD RAMP	YES
TEST WAFER ID	SYSTEM
MEAN THICK	47.5
S.D. THICK	.7

READ ME 7011 05/04/91
HLLT
RLLT
COMMENT : SI-BRIDGE OK

Lot number : PLINE240/1
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

READ ME 7011 05/04/91
 MVOU

G_DOX 975 8438 05/04/91

HLLT

COMMENT : DERDE WAFERLABELING NIET LEESBAAR IN SPEC

RLLT

MVOU I-4

# WAFERS	4
FUR TYPE	DRY
DRY OXIDTEMP	975
DRY OXID TIM	90
STANDARDRAMP	YES
TESTWAFER ID	SYSTEEM
MEAN THICK	49.8
S.D. THICK	1.1

THK_MEAS_8 7358 08/04/91
 MVOU LEITZ

# WAFERS	4
TESTWAFER ID	S3CM1/18,20
MEAN THICK	29.7
S.D. THICK	.4
DEVICEWAFER1	S3CM1/18
THICKNESS1	29.8
THICKNESS1	30.0
THICKNESS1	29.2
THICKNESS1	30.2
THICKNESS1	29.4
DEVICEWAFER2	S3CM1/20
THICKNESS2	49.5
THICKNESS2	50.1
THICKNESS2	49.2
THICKNESS2	50.8
THICKNESS2	49.8
NOMTHICKNESS	50
GTM ACTION	PASS

I/I-B MU L 3292 08/04/91
 MVOU NV6200

# WAFERS	
ION SPECIES	BORON
IMPLANT DOSE	1500 10

Lot number : PLINE240/1

Product : SOI 3UM CMOS

Route : GW_S3CMOS1

I/I-B MU L 3292 08/04/91

IMP. ENERGY	25
BEAM CURRENT	2
TILT ANGLE	7.0
RUN NUMBER	910408/3
RESIST ON ?	NO
POSTBAKE ?	NO
CHAMBER VAC	450E-08
H2 COOL PRES	3.0
TOTAL TIME	16

I/I-P 1E11 3121 08/04/91

CEDA NV6200

# WAFERS	1
ION SPECIES	BORON
IMPLANT DOSE	200E 10
IMP. ENERGY	25
BEAM CURRENT	*****
TILT ANGLE	7.0
RUN NUMBER	910408/4
RESIST ON ?	NO
POSTBAKE ?	NO
CHAMBER VAC	270E-08
H2 COOL PRES	3.0
TOTAL TIME	22

CEDA NV6200

# WAFERS	2
ION SPECIES	BORON
IMPLANT DOSE	250E 10
IMP. ENERGY	25
BEAM CURRENT	2
TILT ANGLE	7.0
RUN NUMBER	910408
RESIST ON ?	NO
POSTBAKE ?	NO
CHAMBER VAC	314E-08
H2 COOL PRES	3.0
TOTAL TIME	28

MVOU NV6200

# WAFERS	1
ION SPECIES	PHOSPHORUS
IMPLANT DOSE	100E 10
IMP. ENERGY	25
BEAM CURRENT	2
TILT ANGLE	7.0
RUN NUMBER	910408
RESIST ON ?	NO

Lot number : PLINE240/1
Product : SOI 3UM CMOS
Route : GW_S3CMOS1

I/I-P 1E11 3121 08/04/91

POSTBAKE ?	NO
CHAMBER VAC	515E-08
H2 COOL PRES	2.0
TOTAL TIME	60

MERGE LOT 0950 08/04/91
MRLT

UNITS used :

Oven times are in minutes
Sputter times are in seconds
Etch times per wafer are in seconds
Strip times are in minutes
Temperatures are in degrees Celsius
Dimensions are in nm
Implant dose (ions/cm2); Implant Energy (KeV); Beam current (uA)

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

PRD INFO 7000 25/02/91
 ORLT
 MVOU

WFR SELECT 7001 26/02/91
 MVOU KRASPEN LABEL S3CM2/1-20

THK MEAS 1 7351 26/02/91
 MVOU LEITZ # WAFERS 10
 DEVICEWAFER1 ALL SOI
 NOMTHICKNESS 200
 GTM ACTION PASS

COMMENT : SEE LTHL FOR SI-THICKNESSES.

FULL CLEAN 7001 27/02/91
 MVOU MERCURY # WAFERS 16
 CLEAN TYPE FULL

Dry Clean 8640 27/02/91
 MVOU 1-3 # WAFERS 10
 FUR TYPE DRY
 DRY OXIDTEMP 1000
 DRY OXID TIM 180
 STANDARDRAMP YES
 TESTWAFER ID SYSTEEM
 MEAN THICK 101.6
 S.D. THICK 2.1

WETCH OX 7101 27/02/91
 MVOU WET BENCH # WAFERS 10
 WETETCHSTUFF THOX
 WET ETCHANT BHF
 TEMPERATURE 22.0
 DEVICEWAFER 7-16
 DEVWAFETCTIM 110

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

WETCH OX 7101 27/02/91

THK_MEAS_2 7352 27/02/91

MVOU

LEITZ

WAFERS

10

NOMTHICKNESS

160

GTM ACTION

PASS

COMMENT : MEASUREMENTS SEE LTHL. MEASURED ON VS/VIS.

D_OX 1000 8641 28/02/91

MVOU

I-3

WAFERS

10

FUR TYPE

DRY

DRY OXIDTEMP

1000

DRY OXID TIM

32

STANDARD RAMP

YES

TEST WAFER ID

SYSTEEM

MEAN THICK

31.1

S.D. THICK

.9

WETCH OX 7102 28/02/91

HLLT

RLLT

MVOU

WET BENCH

WAFERS

5

WETETCHSTUFF

THOX

WET ETCHANT

BHF

TEMPERATURE

22.0

DEVICE WAFER

12-16

DEVWAFETCTIM

43

THK_MEAS_3 7353 04/03/91

MVOU

LEITZ

WAFERS

5

DEVICE WAFER1

12-16

NOMTHICKNESS

142

GTM ACTION

PASS

D_OX 1000 8642 04/03/91

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

D_OX 1000 8642 04/03/91
 MVOU I-3

# WAFERS	15
FUR TYPE	DRY
DRY OXIDTEMP	1000
DRY OXID TIM	31
STANDARDRAMP	YES
TESTWAFER ID	SYSTEEM
MEAN THICK	30.5
S.D. THICK	.4

THK_MEAS_4 7354 05/03/91
 MVOU LEITZ

# WAFERS	4
TESTWAFER ID	S3CM1/17-20
NOMTHICKNESS	30
GTM ACTION	PASS

COMMENT ANNOTATION : 17: C:32.9 N:33.4 Z:33.9 O:32.7 W:32.5
 18: C:33.9 N:32.7 Z:32.7 O:32.9 W:32.3
 19: C:32.5 N:32.5 Z:32.5 O:32.7 W:32.3
 20: C:32.7 N:32.5 Z:33.2 O:33.0 W:32.1
 PLINE240
 WAFER S3CM1/16 VERTOONT ZWARTE VLEKJES
 (HET IS GEEN RESIST)

COMMENT : MEASUREMENTS SEE LTHL (ALTH).

NITR DEP 1201 05/03/91
 MVOU NITRIDE

# WAFERS	20
CLEAN WIP	BASIC
FILM TYPE	NITRIDE
STANDARD.?	YES
DEPOSIT TIME	99
MEAN THICK S	204.7
S.D. THICK S	2.9
TESTWAFER ID	SYSTEEM
PARTICLE TOT	65
PARTICLE_CM2	.78
AREA	.32
PART_RANGE_1	59
PART_RANGE_2	3
PART_RANGE_3	
PART_RANGE_4	

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

NITR DEP 1201 05/03/91

PART RANGE 5	
PART RANGE 6	
PART RANGE 7	
PART RANGE 8	
PART RANGE 9	1
PART RANGE 0	2
S D PARTIC.	239.57
EXCLUSION	10

THK_MEAS 5 7355 05/03/91
 MVOU SPECTRAMAP

# WAFERS	4
TESTWAFER ID	S3CM1/17-20
NOMTHICKNESS	200
GTM ACTION	PASS

COMMENT : MEASUREMENTS SEE LTHL (ALTH).

CANON PR 1 6101 05/03/91
 MVOU CANON

# WAFERS	16
# TIMES	1
DEHYD TEMP	200
SOFTBAK TEMP	110
PHOTORESIST	S1713
MASK ID	SOI ACT
EXPOSE TIME	35.00
SUBSTRATE	NITRIDE
D.U.V. TIME	.00
POSTBAKETEMP	95
POST METHOD	HOTFLATE
DEVELOPMENT	TRACK
RESIST SPEED	4300
VISUAL_INSP	PASS
OXYGEN FLASH	NO

INSP PH 1 7311 06/03/91
 MVOU MICROSCOPE

# WAFERS	5
PFI EXAMINE	50
PFI PASS	50
PFI FAIL	
PFI MARGINAL	

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

INSP PH 1 7311 06/03/91

PEI ACTION PASS

COMMENT : SI TOP LAYER FULL OF SI-DEFECTS (STAPELFOUTEN).

NIT D.ETCH 4201 07/03/91
 MVOU DUAL

# WAFERS	16
RECIPE ID	NI ETCH
LOGBOOK REF	91/58
DRYNITRSTUFF	NITRIDE
ETCH TIME	1105.00
VISUAL INSP	PASS
MASK COND..	GOOD
ETCHSTOPLEFT	30.4
ETCHSTOPLEFT	29.8
ETCHSTOPLEFT	29.0
ETCHSTOPLEFT	29.8
ETCHSTOPLEFT	31.3

POST ETCH1 7331 08/03/91
 MVOU MICROSCOPE

# WAFERS	6
PEI EXAMINE	60
PEI PASS	55
PEI FAIL	
PEI MARGINAL	55
PEI ACTION	PASS

COMMENT : WAFER 16: VLEKKEN!

DRY US STE 7421 11/03/91
 MVOU PRS800

# WAFERS	16
DRYSTRIP TIME	30.00
WETSTRIPSTUF	MICRO2001
WETSTRIP TIME	30
ULTRASON PWR	100.0
VISUAL INSP	PASS

WETCH OX 7103 11/03/91
 MVOU WET BENCH

# WAFERS	16
WETETCHSTUFF	THOV

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

WETCH OX 7103 11/03/91

NET ETCHANT	BHF	
TEMPERATURE		22.0
TESTWAFER ID	S3CM1/1	
TESTWAFETCTIM		35
DEVICEWAFER	S3CM1/2-16	
DEVWAFETCTIM		35

COMMENT : BHF ETCHTIME: 29" + 6" = 35".

CANON PR 2 6102 12/03/91
 MVOU CANON

# WAFERS	5
# TIMES	1
DEHYD TEMP	200
SOFTBAK TEMP	110
PHOTORESIST	S1713
MASK ID	SOI NCHAN VT
EXPOSE TIME	43.00
SUBSTRATE	SI/NITRIDE
D.U.V. TIME	10.00
POSTBAKETEMP	150
POST METHOD	OVEN
DEVELOPMENT	TRACK
RESIST SPEED	4300
VISUAL INSP	PASS
OXYGEN FLASH	NO

INSP PH 2 7312 12/03/91
 MVOU MICROSCOPE

# WAFERS	5
PPI EXAMINE	30
PPI PASS	30
PPI FAIL	
PPI MARGINAL	
PPI ACTION	PASS

IMI-B 1E14 3250 13/03/91
 MVOU NV6200

# WAFERS	12
ION SPECIES	BORON
IMPLANT DOSE	400E 12
IMP. ENERGY	50
BEAM CURRENT	111

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

I/I B 1E14 3250 13/03/91

TILT ANGLE	7.0
RUN NUMBER	010313
RESIST ON ?	YES
POSTBAKE ?	NO
TOTAL TIME	90

DRY US STR 7422 13/03/91
 MVOU PRS800

# WAFERS	5
DRYSTRIP TIME	60.00
E STRIP TEMP	199.00
WETSTRIPSTUF	MICRO2001
WETSTRIP TIME	30
ULTRASON PWR	100.0
VISUAL INSP	PASS

C ANN 950 8330 14/03/91
 MVOU I-2

# WAFERS	4
FUR TYPE	ANN
ANNEAL TEMP	950
ANNEAL TIME	90
STANDARD RAMP	YES

SI ETCH 4001 21/03/91
 MVOU DUAL

# WAFERS	10
RECIPE ID	SI ETCH
LOGBOOK REF	91/77
DRYSIXTSTUFF	SI XTAL
ETCH TIME	420.00
VISUAL INSP	PASS
MASK COND..	GOOD

POST ETCH2 7332 25/03/91
 MVOU MICROSCOPE

# WAFERS	6
PEI EXAMINE	60
PEI PASS	60
PEI FAIL	
PEI MARGINAL	

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

POST_ETCH2 7332 25/03/91

PEI ACTION PASS

COMMENT : FOX MEASURED ON WAFERS 9.14.11: 172 400NM.

C_WOX 1000 8140 25/03/91
 MVOU I-2

# WAFERS	10
FUR TYPE	WET
WET OXIDTEMP	1000
WET OXID TIM	138
STANDARD RAMP	YES
TEST WAFER ID	SYSTEM
MEAN THICK	592.4
S.D. THICK	2.7

C_WOX 1000 8141 26/03/91
 MVOU I-1

# WAFERS	11
FUR TYPE	WET
WET OXIDTEMP	1000
WET OXID TIM	75
STANDARD RAMP	YES
TEST WAFER ID	SYSTEM
MEAN THICK	393.1
S.D. THICK	4.9

THE_MEAS_6 7356 27/03/91
 MVOU LEITZ

# WAFERS	4
DEVICE WAFER1	S3CM1/1
THICKNESS1	584.9
THICKNESS1	588.0
THICKNESS1	587.4
THICKNESS1	586.6
THICKNESS1	587.3
DEVICE WAFER2	S3CM1/4
THICKNESS2	588.7
THICKNESS2	591.8
THICKNESS2	590.1
THICKNESS2	592.2
THICKNESS2	588.5
NOM THICKNESS	600
GTM ACTION	PASS

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW S3CMOS1

THK_MEAS_6 7356 27/03/91

C_WOX 1000 8142 27/03/91
 CEDA LEITZ

WAFERS 4
 DEVICEWAFER1 S3CM1/7
 THICKNESS1 653.0
 THICKNESS1 641.2
 THICKNESS1 640.8
 THICKNESS1 629.9
 THICKNESS1 638.0
 DEVICEWAFER2 S3CM1/12
 THICKNESS2 647.0
 THICKNESS2 643.3
 THICKNESS2 632.8
 THICKNESS2 625.4
 THICKNESS2 635.0
 NOMTHICKNESS 633
 GTM ACTION PASS

COMMENT : FOX ON SOI-WAFERS: .THICKNESS=THOX SI-FILM-INTERMEDIATE OX
 MVNS I-1 # WAFERS

WET OXID TIM

COMMENT : NO ADDITIONAL FIELD OXIDATION IS NEEDED.

WETCH NITR 1121 27/03/91
 MVOU WET BENCH

WAFERS 20
 WETETCHSTUFF THOX
 WET ETCHANT BHF
 DEVWAFETCTIM 20
 WETCHSTUFF 1 NITRIDE
 WET ETCHANT1 TRANSETCH
 DEVWAFETTIM1 60

COMMENT :

SPLIT LOT 0900 27/03/91
 SPLT
 MVOU

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

SPLIT LOT 0900 27/03/91
 I/I-P 1E11 3100 28/03/91
 MVOU NV6200

# WAFERS	3
ION SPECIES	PHOSPHORUS
IMPLANT DOSE	100E 09
IMP. ENERGY	100
BEAM CURRENT	
TILT ANGLE	7.0
RUN NUMBER	910328/4
RESIST ON ?	NO
POSTBAKE ?	NO
CHAMBER VAC	586E-09
H2 COOL PRES	1.5
TOTAL TIME	17

G_DOX 975 8435 29/03/91
 MVOU I-4

# WAFERS	12
FUR TYPE	DRY
DRY OXIDTEMP	975
DRY OXID TIM	90
STANDARD RAMP	YES
TESTWAFER ID	SYSTEM
MEAN THICK	53.6
S.D. THICK	3.8
TESTWAF ID 2	T17
MEAN THICK 2	52.3
S.D. THICK 2	1.4

I/I-B MU L 3290 29/03/91
 MVOU NV6200

# WAFERS	5
ION SPECIES	BORON
IMPLANT DOSE	100E 09
IMP. ENERGY	25
BEAM CURRENT	
TILT ANGLE	7.0
RUN NUMBER	910329/4
RESIST ON ?	NO
POSTBAKE ?	NO
CHAMBER VAC	326E-08
H2 COOL PRES	2.0
TOTAL TIME	13

Lot number : PLINE240
Product : SOI 3UM CMOS
Route : GW_S3CMOS1

THK_MEAS 7	7357	03/04/91		
MVOU	LEITZ		# WAFERS	2
			TESTWAFER ID	17.10
			NOMTHICKNESS	50
			QTM ACTION	PASS

COMMENT ANNOTATION :

S3CM1/17: C=49.9 N=48.8 Z=49.7 O=49.4 W=48.7

S3CM1/19: C=48.9 N=49.9 Z=49.5 O=49.1 W=49.0

CANON PR 3	6103	03/04/91		
MVOU	CANON		# WAFERS	4
			# TIMES	1
			DEHYD TEMP	200
			SOFTBAK TEMP	110
			PHOTORESIST	S1713
			MASK ID	SOI N CH VT
			EXPOSE TIME	40.00
			SUBSTRATE	THOX
			D.U.V. TIME	10.00
			POSTBAKETEMP	150
			POST METHOD	OVEN
			DEVELOPMENT	TRACK
			RESIST_SPEED	4300
			VISUAL_INSP	PASS
			OXYGEN FLASH	NO

INSP PH 2	7313	04/04/91		
MVOU	MICROSCOPE		# WAFERS	4
			PFI EXAMINE	20
			PFI PASS	20
			PFI FAIL	
			PFI MARGINAL	
			PFI ACTION	PASS

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

INSP PH 3 7313 04/04/91
 I/I-B MU L 3291 04/04/91
 MV0U NV6200

WAFERS 3
 ION SPECIES BORON
 IMPLANT DOSE 100E 10
 IMP. ENERGY 170
 BEAM CURRENT 2
 TILT ANGLE 7.0
 RUN NUMBER 91040473
 RESIST ON ? NO
 POSTBAKE ? NO
 CHAMBER VAC 419E-08
 H2 COOL PRES 3.0
 TOTAL TIME 16

DRY US STR 7423 04/04/91
 CEDA NV6200

WAFERS 2
 ION SPECIES BORON
 IMPLANT DOSE 600E 09
 IMP. ENERGY 30
 BEAM CURRENT 1
 TILT ANGLE 7.0
 RUN NUMBER 91040474
 RESIST ON ? YES
 POSTBAKE ? NO
 CHAMBER VAC 463E-09
 H2 COOL PRES 3.0
 TOTAL TIME 19

CEDA NV6200

WAFERS 3
 ION SPECIES BORON
 IMPLANT DOSE 600E 09
 IMP. ENERGY 30
 BEAM CURRENT 1
 TILT ANGLE 7.0
 RUN NUMBER 91040475
 RESIST ON ? YES
 POSTBAKE ? NO
 CHAMBER VAC 503E-09
 H2 COOL PRES 3.0
 TOTAL TIME 22

CEDA NV6200

WAFERS 2
 ION SPECIES BORON
 IMPLANT DOSE 100E 10
 IMP. ENERGY 30

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

DRY US STR 7423 04/04/91

MVOU PRS800

BEAM CURRENT 2
 TILT ANGLE 7.0
 RUN NUMBER 81040246
 RESIST ON ? YES
 POSTBANE ? NO
 CHAMBER VAC 537E-09
 H2 COOL PRES 3.0
 TOTAL TIME 14
 # WAFERS 4
 DRYSTRIPTIME 30.00
 E STRIP TEMP 166.00
 WETSTRIPSTUF MICRO2000
 WETSTRIPTIME 30
 ULTRASON PWR 100.0
 VISUAL INSP PASS

COMMENT : WAFER S3CM1-16:LITTLE SPOTS IN FIELD REGIONS: NOT RESIST.

JUMP TO OP 0600 05/04/91
 MINS

MERGE LOT 0650 08/04/91
 MELT
 MVOU

POLY GATE 1101 09/04/91
 MVOU POLY

WAFERS 20
 CLEAN WIP BASIC
 FILM TYPE POLY
 STANDARD.? YES
 DEPOSIT TIME 38.1
 MEAN THICK S 147.4
 S.D. THICK S 1.6
 TESTWAFER ID SYSTEEM

THK_MEAS_2 0350 10/04/91
 MVOU LEITE

WAFERS 4
 TESTWAFER ID S3CM1-17-20

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

THK_MEAS_9 7359 09/04/91

DEVICEWAFER1	S3CM1/17	
THICKNESS1		447.9
THICKNESS1		447.9
THICKNESS1		449.9
THICKNESS1		448.9
THICKNESS1		450.3
DEVICEWAFER2	S3CM1/18	
THICKNESS2		446.4
THICKNESS2		446.4
THICKNESS2		447.9
THICKNESS2		446.4
THICKNESS2		448.6
NOMTHICKNESS		450
GTM ACTION	PASS	

COMMENT ANNOTATION : VALUE CHANGED FOR PARAMETER THICKNESS2
 UNIT Centre
 FROM 444.9 TO 446.4
 VALUE CHANGED FOR PARAMETER THICKNESS2
 UNIT East
 FROM 444.6 TO 446.4
 VALUE CHANGED FOR PARAMETER THICKNESS2
 UNIT North
 FROM 448.9 TO 447.9
 VALUE CHANGED FOR PARAMETER THICKNESS2
 UNIT South
 FROM 445.7 TO 446.4
 VALUE CHANGED FOR PARAMETER THICKNESS2
 UNIT West
 FROM 448.9 TO 448.6
 VALUE CHANGED FOR PARAMETER # WAFERS
 UNIT
 FROM 15 TO 19

COAT FRONT 6901 09/04/91
 CEDA LEITZ

# WAFERS	4
TESTWAFER ID	S3CM1/17-20
DEVICEWAFER1	S3CM1/19
THICKNESS1	444.9
THICKNESS1	444.6
THICKNESS1	448.9
THICKNESS1	445.7

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

COAT FRONT 6901 09/04/91

THICKNESS1		446.9
DEVICEMAFER2	S3CM1/20	
THICKNESS2		445.3
THICKNESS2		444.9
THICKNESS2		449.9
THICKNESS2		447.0
THICKNESS2		449.9
NOMTHICKNESS		450
GTM ACTION	PASS	
# WAFERS		19
# TIMES		1
DEHYD TEMP		200
MISCSPINSTUF	S3413	
RESIST_SPEED		4600
D.U.V. TIME		.00
POSTBAKETEMP		150
POST METHOD	OVEN	
POSTBAKETIME	150E-01	

MVOU MTI

WETCH POLY 7111 09/04/91
 MVOU WET BENCH

# WAFERS		19
WETETCHSTUFF	POLY	
WET ETCHANT	POLYETCHSTUF	
TEMPERATURE		22.0
TESTWAFER ID	S3CM1/20	
TESWAFETCTIM		120
DEVICEMAFER	ALL	
DEVWAFETCTIM		190

COMMENT : BEFORE POLY WET ETCH, A BHF DIP OF 10" IS DONE.

WETCH OX 7105 09/04/91
 MVOU WET BENCH

# WAFERS		19
WETETCHSTUFF	THOX	
WET ETCHANT	BHF	
TEMPERATURE		22.0
TESTWAFER ID	S3CM1/20	
TESWAFETCTIM		58
DEVICEMAFER	ALL	
DEVWAFETCTIM		56

Lot number : PLINE240
Product : SOI 3UM CMOS
Route : GW_S3CMOS1

DRY US STR 7425 10/04/91
MVOU PRS800

# WAFERS	19
DRYSTRIP TIME	20.00
E STRIP TEMP	165.00
WETSTRIPSTUF	MICRO2000
WETSTRIP TIME	30
ULTRASON PWR	1.0
VISUAL INSP	PASS

I/I-P 1E16 3170 12/04/91
MVOU NV6200

# WAFERS	19
ION SPECIES	PHOSPHORUS
IMPLANT DOSE	100E 14
IMP. ENERGY	50
BEAM CURRENT	700
TILT ANGLE	7.0
RUN NUMBER	910411/1
RESIST ON ?	NO
POSTBAKE ?	NO
CHAMBER VAC	400E-06
H2 COOL PRES	2.0
TOTAL TIME	334

C_ANN 800 8300 12/04/91
MVOU I-2

# WAFERS	12
FUR TYPE	ANN
ANNEAL TEMP	800
ANNEAL TIME	45
STANDARD RAMP	YES

COMMENT : SRCM1/5 GEBROKEN IN OVEN

C_ANN 800 8301 12/04/91
MVOU I-2

# WAFERS	7
FUR TYPE	ANN
ANNEAL TEMP	800
ANNEAL TIME	240
STANDARD RAMP	YES

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

WETCH OX	7106	15/04/91	# WAFERS	18
MVOU	WET BENCH		WETETCHSTUFF	THON
			WET ETCHANT	BHF
			TEMPERATURE	22.0
			TESTWAFER ID	S3CM1/17-20
			TESWAFETCTIM	14
			DEVICEWAFER	ALL -(5.12)
			DEVWAFETCTIM	14

RES_MEAS_1	7371	15/04/91	# WAFERS	1
CEDA	FOURDIM		TESTWAFER ID	S3CM1/19
			MEAN RESISVY	190E 00
			S.D. RESISVY	224E-02
			GRM ACTION	PASS
MVOU	FOURDIM		# WAFERS	1
			TESTWAFER ID	S3CM1/20
			MEAN RESISVY	140E 00
			S.D. RESISVY	314E-02
			GRM ACTION	PASS

CANON PR 5	6105	24/04/91	# WAFERS	14
MVOU	CANON		# TIMES	1
			DEHYD TEMP	200
			SOFTBAK TEMP	110
			PHOTORESIST	S1713
			MASK ID	SOI POLY
			EXPOSE TIME	24.00
			SUBSTRATE	POLY
			D.U.V. TIME	.00
			POSTBAKETEMP	95
			POST METHOD	HOTPLATE
			DEVELOPMENT	TRACK
			RESIST SPEED	4300
			VISUAL INSP	PASS
			OXYGEN FLASH	NO

Lot number : PLINE240
Product : SOI 3UM CMOS
Route : GW_S3CMOS1

INSP PH 5 7315 24/04/91
 MVOU MICROSCOPE

# WAFERS	5
PPI EXAMINE	50
PPI PASS	50
PPI FAIL	
PPI MARGINAL	
PPI ACTION	PASS

PLY_1511e 4102 26/04/91
 MVOU TEGAL

# WAFERS	14
RECIPE ID	HBR-ETCH
LOGBOOK REF	91/121
DRYPOLYSTUFF	POLY
ETCH_TIM_BRK	18
ETCH_TIM_BLK	30
ETCH_TIM_OVN	120
DEVWAF_MV_1	518.3
DEVWAF_SD_1	5.3
DEVWAF_MV_2	565.2
DEVWAF_SD_2	10.3
VISUAL_INSP	PASS
MASK COND..	GOOD

POST_ETCH3 7333 29/04/91
 MVOU MICROSCOPE

# WAFERS	7
PEI EXAMINE	42
PEI PASS	42
PEI FAIL	
PEI MARGINAL	
PEI ACTION	PASS

COMMENT : GAA TRNSTRS:ON A LOT OF THEM: BLACK DOTS AT THE EDGE OF A.A.

DRY_US_STR 7426 03/05/91
 MVOU FRS800

# WAFERS	14
DRYSTRIP TIME	60.00
E STRIP TEMP	149.00
WETSTRIPSTUF	MICRO2000

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

DRY US STR 7426 03/05/91

WETSTRIP TIME 5.1
 ULTRASON PWF 1.2
 VISUAL INSP PASS

COMMENT ANNOTATION : WAFERS 7-11: AFTER SUPPLEMENTARY DRY + WET
 STRIP: STILL VERY FEW PIECES OF THIN BLACK
 "WIRES" AT THE EDGE OF SOME POLY STRUCTURES
 OF THE AAG-WAFERS.

1: C=37.9 N=39.1 Z=38.9 O=38.3 W=39.2
 2: C=39.8 N=40.3 Z=39.5 O=39.4 W=39.6
 3: C=38.0 N=39.1 Z=38.9 O=36.7 W=38.4
 4: C=37.7 N=38.8 Z=38.4 O=37.7 W=38.8
 6: C=40.6 N=41.4 Z=42.0 O=40.2 W=41.0
 17: C=40.2 N=42.0 Z=41.2 O=42.0 W=41.0
 18: C=20.6 N=22.1 Z=23.1 O=23.0 W=22.3

COMMENT : ALL WAFERS: 2 X (DRY:30' +WET:30' STRIP). 7-11: - DRY: 30'.

THK_MEAS10 7360 03/05/91
 MVOU LEITZ

WAFERS 7
 TESTWAFER ID 17
 MEAN THICK 38.7
 S.D. THICK .6
 DEVICEWAFER1 1-4.6
 NOMTHICKNESS 40
 GTM ACTION PASS

WETCH OX 7107 06/05/91
 MVOU LEITZ

WAFERS 6
 WETETCHSTUFF THOX
 WET ETCHANT 3%HT
 TEMPERATURE 22.0
 TESTWAFER ID 17
 TESWAFETCTIM 104
 DEVICEWAFER ALL
 DEVWAFETCTIM 87

COMMENT ANNOTATION : S3CM1/1: C=17.2 N=18.4 Z=18.6 O=19.1 W=20.9
 S3CM1/2: C=18.8 N=20.1 Z=19.5 O=20.1 W=20.1
 S3CM1/3: C=18.2 N=20.0 Z=18.7 O=18.0 W=19.8
 S3CM1/4: C=18.4 N=17.3 Z=20.7 O=19.5 W=20.1

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

WETCH OX 7107 06/05/91
 SACM100: 0=20.0 1=20.0 2=20.0 3=20.0 4=20.0

CANON PR 6	6106	06/05/91		
MVOU	CANON		# WAFERS	4
			# TIMES	1
			DEHYD TEMP	200
			SOFTBAK TEMP	110
			PHOTORESIST	S1713
			MASK ID	SOI NPLUS
			EXPOSE TIME	31.00
			SUBSTRATE	THOX
			D.U.V. TIME	10.00
			POSTBAKETEMP	150
			POST METHOD	OVEN
			DEVELOPMENT	TRACK
			RESIST_SPEED	4300
			VISUAL_INSP	PASS
			OXYGEN FLASH	NO

INSP PH 6	7316	07/05/91		
MVOU	MICROSCOPE		# WAFERS	4
			PPI EXAMINE	20
			PPI PASS	20
			PPI FAIL	
			PPI MARGINAL	
			PPI ACTION	PASS

I/I-F MU H	3195	07/05/91		
MVOU	NV6200		# WAFERS	11
			ION SPECIES	PHOSPHORUS
			IMPLANT DOSE	400E 13
			IMP. ENERGY	70
			BEAM CURRENT	300
			TILT ANGLE	2.0
			RUN NUMBER	010507/2
			PESIST ON ?	YES
			POSTBAKE ?	NO
			CHAMBER VAC	700E-06
			HE COOL PRES	1.0

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

I/I-P MU H 3195 08/05/91

TOTAL TIME 131

DRY US STR 7427 08/05/91
 MVOU PRS800

WAFERS 4
 DRYSTRIPTIME 60.00
 E STRIP TEMP 189.00
 WETSTRIPSTUF MICRO2000
 WETSTRIPTIME 30
 ULTRASON PWR 10
 VISUAL INSP PASS

COMMENT : ON WAFER S3CM1/13: ON A FEW PLACES: (POLY PRINT OF) RUBBISH.

CANON PR 7 6107 08/05/91
 MVOU CANON

WAFERS 4
 # TIMES 1
 DEHYD TEMP 200
 SOFTBAK TEMP 110
 PHOTORESIST S1713
 MASK ID SOI P PLUS
 EXPOSE TIME 32.00
 SUBSTRATE THOX
 D.U.V. TIME 10.00
 POSTBAKETEMP 150
 POST METHOD OVEN
 DEVELOPMENT TRACK
 RESIST SPEED 4300
 VISUAL INSP PASS
 OXYGEN FLASH NO

INSP PH 7 7317 08/05/91
 MVOU MICROSCOPE

WAFERS 4
 PPI EXAMINE 20
 PPI PASS 20
 PPI FAIL
 PPI MARGINAL
 PPI ACTION PASS

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

I-I-B MU H 3295 13/05/91
 MVOU NV6200

# WAFERS	7
ION SPECIES	BORON
IMPLANT DOSE	400E 12
IMP. ENERGY	25
BEAM CURRENT	181
TILT ANGLE	7.0
RUN NUMBER	910513/2
RESIST ON ?	YES
POSTBAKE ?	YES
CHAMBER VAC	500E-08
H2 COOL PRES	3.0
TOTAL TIME	552

DRY US STR 7428 14/05/91
 MVOU PRS800

# WAFERS	4
DRYSTRIP TIME	60.00
WETSTRIPSTUF	MICRO2001
WETSTRIP TIME	30
ULTRASON PWR	.0
VISUAL INSP	PASS

C_ANN 800 8302 14/05/91
 MVOU I-2

# WAFERS	14
FUR TYPE	ANN
ANNEAL TEMP	800
ANNEAL TIME	180
STANDARD DRAMP	YES

TEOS UNSG 1001 15/05/91
 MVOU TEOS

# WAFERS	16
FILM TYPE	USG
STANDARD.?	YES
DEPOSIT TIME	56.6
MEAN THICK S	603.1
S.D. THICK S	5.6
PARTICLE TOT	62
PARTICLE_CM2	.74
AREA	.00

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

TEOS UNSG 1001 15/05/91

PART_RANGE_1	47
PART_RANGE_2	14
PART_RANGE_3	1
PART_RANGE_4	
PART_RANGE_5	
PART_RANGE_6	
PART_RANGE_7	
PART_RANGE_8	
PART_RANGE_9	
PART_RANGE_0	
S D PARTIC.	62.60
EXCLUSION	10

C_ANN 800 8303 15/05/91
 MVOU I-2

# WAFERS	16
FUR TYPE	ANN
ANNEAL TEMP	800
ANNEAL TIME	30
STANDARDRAMP	YES

CANON PR 8 6108 15/05/91
 MVOU CANON

# WAFERS	16
# TIMES	1
DEHYD TEMP	200
SOFTBAK TEMP	110
PHOTORESIST	S1713
MASK ID	SOI CONTACT
EXPOSE TIME	35.80
SUBSTRATE	UTEOS
D.U.V. TIME	5.00
POSTBAKETEMP	150
POST METHOD	OVEN
DEVELOPMENT	TRACK
RESIST SPEED	4300
VISUAL_INSP	PASS
OXYGEN FLASH	NO

INSP PH 8 7318 16/05/91

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

INSP PH 8 7318 16/05/91
 MVOU MICROSCOPE

WAFERS 4
 PPI EXAMINE 10
 PPI PASS 10
 PPI FAIL
 PPI MARGINAL
 PPI ACTION PASS

COMMENT : CONTROLE OP:1,3,9,16. OP 1,3:SPORADISCH KLEINE LAKVLIESJES(?)

WETCH CA 7108 16/05/91
 MVOU WET BENCH

WAFERS 16
 WETETCHSTUFF UTEOS
 WET ETCHANT BHF
 TEMPERATURE 22.0
 TESTWAFER ID 17.18
 TESWAFETCTIM 180
 DEVICWAFER ALL
 DEWAFETCTIM 200

COMMENT : TEST: 17: 2'45", 18: 3'.

DRY US STR 7429 17/05/91
 MVOU PRS800

WAFERS 14
 DRYSTRIPTIME 30.00
 WETSTRIPSTUF MICRO2001
 WETSTRIPTIME 30
 ULTRASON PWR 1.0
 VISUAL INSP PASS

FRNT ALSI 5201 21/05/91
 MVOU LLS801

WAFERS 14
 SPUTTALSTUFF ALSI
 SPUTTER TEMP WARM
 PROCESS NAME 310H
 TARGET LIFE 32036
 SPUTTER TIME 1100
 TESTWAFER ID TEST06
 MEAN SHEET_R 311E-04
 S.D. SHEET_R 120E-02
 REFLECTIVITY 93
 LAYER_WEIGHT 27.2

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

FRNT ALSI 5201 21/05/91

CANON PR 9 6109 22/05/91
 MV0U CANON

# WAFERS	14
# TIMES	1
DEHYD TEMP	130
SOFTBAK TEMP	110
PHOTORESIST	S1713
MASK ID	SOI 3UM M1
EXPOSE TIME	30.00
SUBSTRATE	AL/SI
D.U.V. TIME	10.00
POSTBAKETEMP	150
POST METHOD	HOTPLATE
DEVELOPMENT	TRACU
RESIST SPEED	4300
VISUAL_INSP	PASS
OXYGEN FLASH	NO

INSP PH 9 5219 23/05/91
 MV0U MICROSCOPE

# WAFERS	7
PPI EXAMINE	50
PPI PASS	50
PPI FAIL	
PPI MARGINAL	
PPI ACTION	PASS

INL D_ETCH 4401 28/05/91
 MV0U INLINE

# WAFERS	14
RECIPE ID	CC01
LOGBOOK REF	217106
DRY_AL_STUFF	ALSI
TOPTIVETCTIM	
ETCH_TIM_BRK	10
ETCH_TIM_END	166
ETCH_TIM_OVN	25
BOTTIVETCTIM	
PASSIV TIME	15
VISUAL_INSP	PASS
MASK COND..	GOOD

Lot number : PLINE240
Product : SOI 3UM CMOS
Route : GW_S3CMOS1

INL D_ETCH 4401 28-05-91

POST_ETCH4 7334 29-05-91
MVOU MICROSCOPE

# WAFERS	14
PEI EXAMINE	32
PEI PASS	32
PEI FAIL	
PEI MARGINAL	
PEI ACTION	PASS

DRY US STR 7430 29-05-91
MVOU PRS800

# WAFERS	14
DRYSTRIP TIME	40.00
E STRIP TEMP	149.00
WETSTRIPSTUF	MICRO2000
WETSTRIP TIME	30
ULTRASON PWR	10
VISUAL INSP	PASS

COMMENT : SUPPLEMENTARY DRY STRIP IN PRS800: 20'.

SINTER 410 9720 29/05/91
MVOU II-4

# WAFERS	3
FUR TYPE	SIN
SINT AMBIENT	FORMINGGAS
TEMPERATURE	420.0
SINTER TIME	20

SINTER 420 9721 29/05/91
MVOU II-4

# WAFERS	14
FUR TYPE	SIN
SINT AMBIENT	FORMINGGAS
TEMPERATURE	420.0
SINTER TIME	20

END PROCES 9999 30/05/91

Lot number : PLINE240
 Product : SOI 3UM CMOS
 Route : GW_S3CMOS1

END RECIPE 0000 00000001
 TEL

 * UNITS used :

: Oven times are in minutes
 : Sputter times are in seconds
 : Etch times per wafer are in seconds
 : Strip times are in minutes
 : Temperatures are in degrees Celsius
 : Dimensions are in nm
 : Implant dose (ions/cm2): Implant Energy (KeV): Beam current (uA)

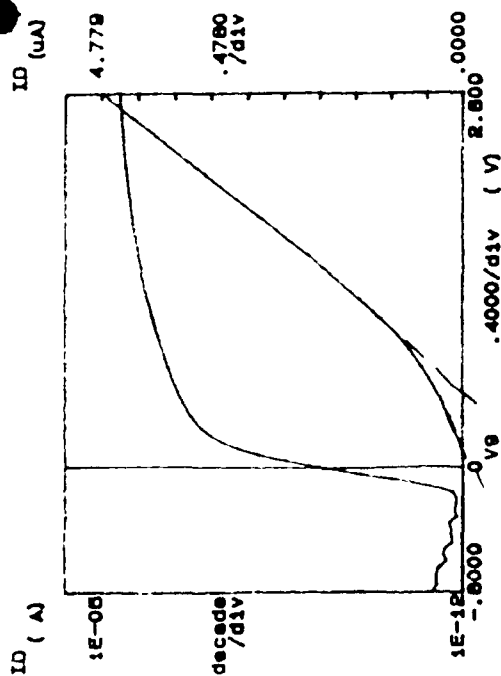
ELECTRICAL CHARACTERISTICS

This Annex reports the electrical characteristics of the GAA devices from the second run (one set of curves for each split) .

These characteristics are:

- $I_D(V_G)$ for $V_{DS} = 100$ mV, with both linear and logarithmic vertical scales (top left Figure)
- $I_D(V_{DS})$ for $V_G = 0$ to 5 volts, (bottom left Figure)
- Transconductance (g_m) at $V_{DS} = 100$ mV, as a function of gate voltage (bottom right Figure)

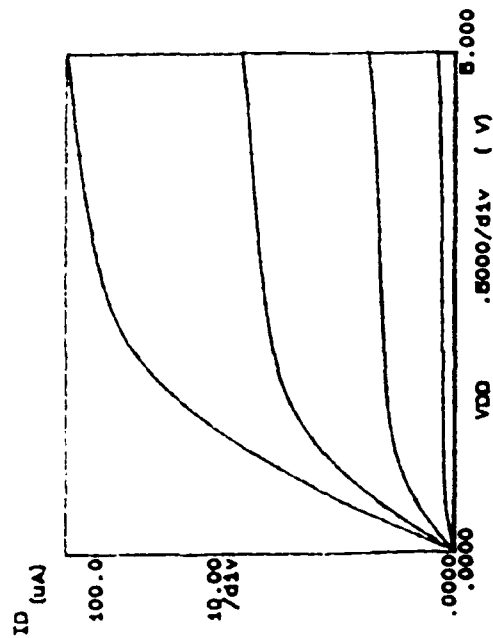
***** GRAPHICS PLOT *****



Variable 1
Vg -Ch3
Linear sweep
Start 0.000V
Stop 1.000V
Step .000V
Variable 2
Vg -Ch4
Linear sweep
Start 0.000V
Stop 1.000V
Step .000V
Constant 1
Vg -Ch1
Vg -Ch2
Vg -Ch3
Vg -Ch4
Vg -Vg1
Vg -Vg2

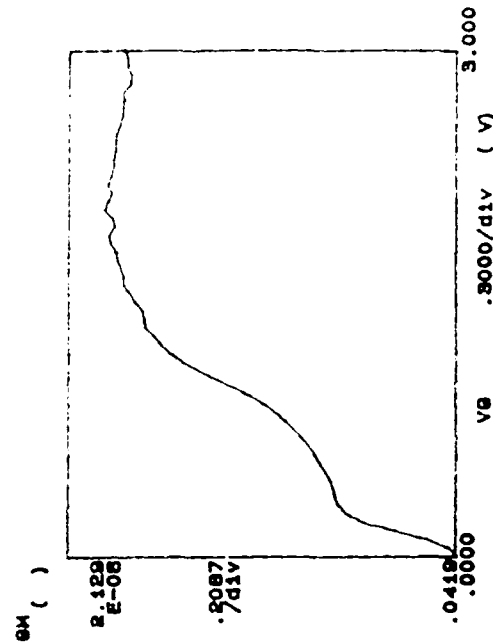
Wager 7
GRA N-ch
tox = 300 Å

***** GRAPHICS PLOT *****



Variable 1
VDD -Ch2
Linear sweep
Start 0.000V
Stop 1.000V
Step .000V
Variable 2
Vg -Ch3
Linear sweep
Start 0.000V
Stop 1.000V
Step .000V
Constant 1
Vg -Ch1
Vg -Ch2
Vg -Ch3
Vg -Ch4
Vg -Vg1
Vg -Vg2

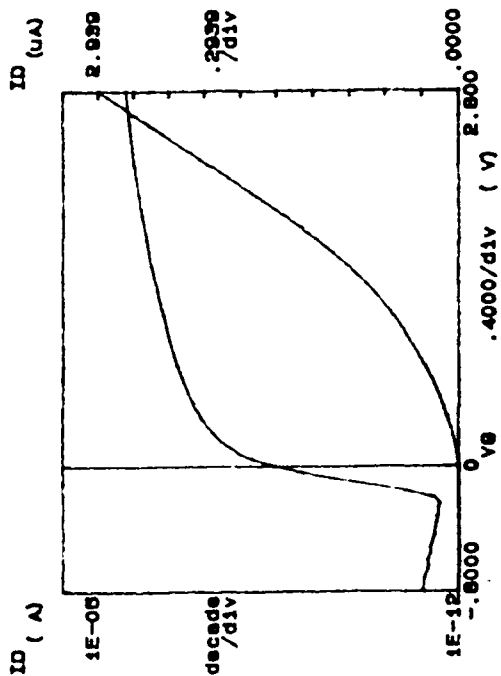
***** GRAPHICS PLOT *****



Variable 1
Vg -Ch3
Linear sweep
Start 0.000V
Stop 1.000V
Step .000V
Constant 1
Vg -Ch1
Vg -Ch2
Vg -Ch3
Vg -Ch4
Vg -Vg1
Vg -Vg2

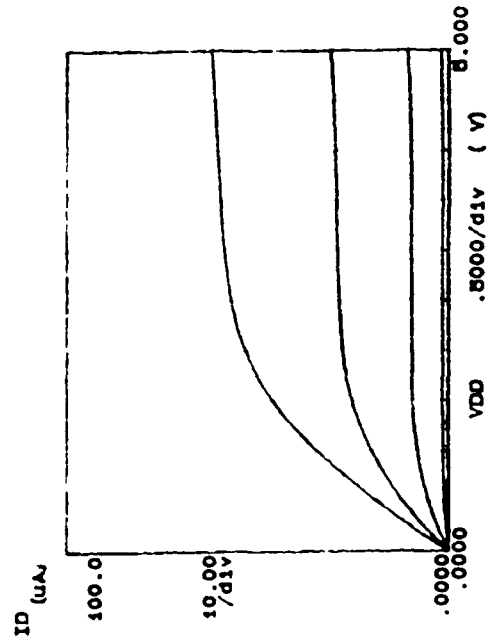
gm () = $\Delta ID / \Delta Vg$

***** GRAPHICS PLOT *****

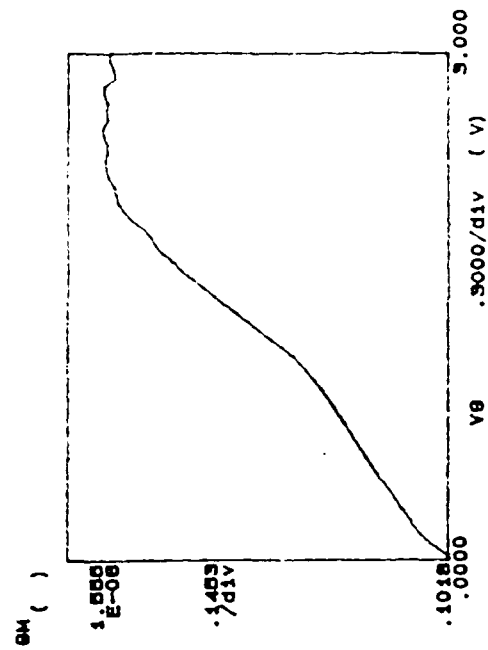


Wafer 10
GAA m-ch
 $t_{ox} = 500 \text{ \AA}$

***** GRAPHICS PLOT *****

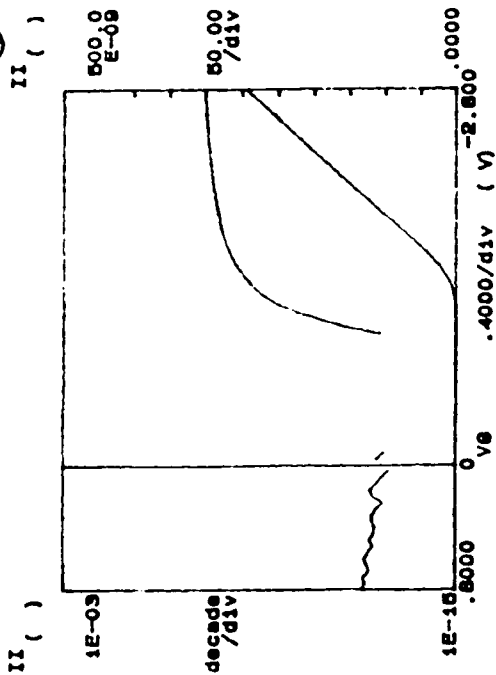


***** GRAPHICS PLOT *****



***** GRAPHICS PLOT *****

()

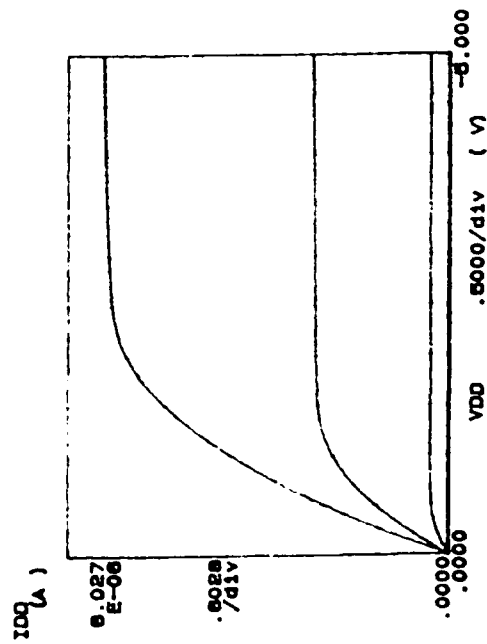
[illegible]

Wage =
GAF P-Ch
Tax = 500

88-1122

***** GRAPHICS PLOT *****

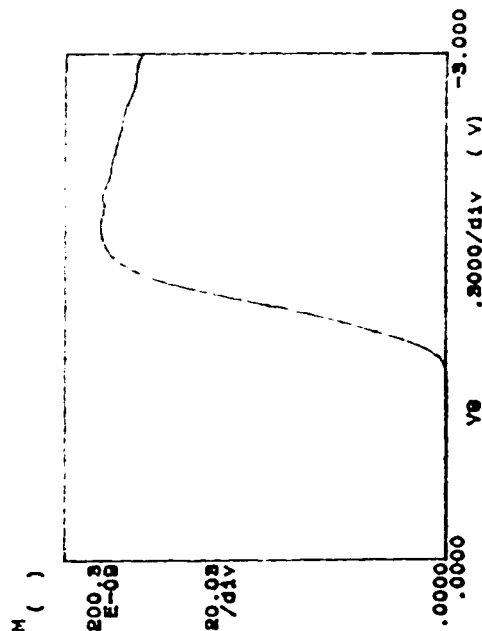
100%



Variable	Unit	Mean	SD	Min	Max
WID	-CH3	0.0000	0.0000	0.0000	0.0000
Linear	mm/mm	0.0000	0.0000	0.0000	0.0000
Start	mm	0.0000	0.0000	0.0000	0.0000
Stop	mm	0.0000	0.0000	0.0000	0.0000
Stop	mm	0.0000	0.0000	0.0000	0.0000
Variable <th>Unit</th> <th>Mean</th> <th>SD</th> <th>Min</th> <th>Max</th>	Unit	Mean	SD	Min	Max
WID	-CH3	0.0000	0.0000	0.0000	0.0000
Linear	mm/mm	0.0000	0.0000	0.0000	0.0000
Start	mm	0.0000	0.0000	0.0000	0.0000
Stop	mm	0.0000	0.0000	0.0000	0.0000
Stop	mm	0.0000	0.0000	0.0000	0.0000
Variable <th>Unit</th> <th>Mean</th> <th>SD</th> <th>Min</th> <th>Max</th>	Unit	Mean	SD	Min	Max
WID	-CH3	0.0000	0.0000	0.0000	0.0000
Linear	mm/mm	0.0000	0.0000	0.0000	0.0000
Start	mm	0.0000	0.0000	0.0000	0.0000
Stop	mm	0.0000	0.0000	0.0000	0.0000
Stop	mm	0.0000	0.0000	0.0000	0.0000

***** GRAPHICS PLOT *****

MO ()



Variable	Value
Q1	10000
Q3	10000
Linear sweep	10000
Start	10000
Stop	10000
Step	10000
Conductance	10000
TSR	10000
TRD	10000
SWA	10000
SWD	10000
TRV	10000
TRW	10000
SWA	10000
SWD	10000
TRV	10000
TRW	10000

88-14753

104 () - 100/100

CHIP LAYOUT

The following pages describe the layout of the GAA chip

c) Transistors with N/P source

W(UM)	L(UM)	NAME	SOURCE	GATE	DRAIN
10.0	3.0	H19	934	935	889
10.0	5.0	H20	936	890	891
50.0	3.0	H21	937	938	892
50.0	5.0	H22	939	893	894

7) Gate all-around transistors

a) Without etch

W(UM)	L(UM)	NAME	SOURCE	GATE	DRAIN
3.0	3.0	C23	359	358	297
3.0	5.0	C24	299	360	298
3.0	10.0	C25	362	361	300
4.0	3.0	C26	302	363	301
4.0	5.0	C27	365	364	303
4.0	10.0	C28	305	366	304

normal SOI

b) Etch L=2.0 UM

W(UM)	L(UM)	NAME	SOURCE	GATE	DRAIN
3.0	3.0	D25	481	480	419
3.0	5.0	D26	421	482	420
3.0	10.0	D27	484	483	422
4.0	3.0	D28	424	485	423
4.0	5.0	D29	487	486	425
4.0	10.0	D30	427	488	426

GAA

c) Etch L=3.0 UM

W(UM)	L(UM)	NAME	SOURCE	GATE	DRAIN
3.0	3.0	E29	603	602	541
3.0	5.0	E30	543	604	542
3.0	10.0	E31	606	605	544
4.0	3.0	E32	546	607	545
4.0	5.0	E33	609	608	547
4.0	10.0	E34	549	610	548

GAA

8) Input protections

a) With PIN-diodes

	NAME	IN	OUT1	OUT2	VDD	VSS
N+ RES	B1	125	186	184	123	185
P+ RES	B2	128	189	187	126	188
INT RES	B3	131	192	190	129	191
POLY RES	B4	134	195	193	132	194

b) With PNN-diodes

	NAME	IN	OUT1	OUT2	VDD	VSS
N+ RES	C1	247	308	306	245	307
P+ RES	B2	250	311	309	248	310
INT RES	B3	253	314	312	251	313
POLY RES	C4	256	317	315	254	316

SAA

SAA

NML

SOI 3UM MPC1

09 METAL 9

